

Title (en)
PHOTORESIST COMPOSITION

Publication
EP 0200141 A3 19880113 (EN)

Application
EP 86105533 A 19860422

Priority
JP 8899885 A 19850426

Abstract (en)
[origin: EP0200141A2] A Photoresist composition consisting essentially of a conjugated diene polymer or its cyclized product, an organic solvent, a photocross-linking agent and a silylating agent.

IPC 1-7
G03F 7/02

IPC 8 full level
G03C 1/00 (2006.01); **G03F 7/004** (2006.01); **G03F 7/038** (2006.01); **G03F 7/075** (2006.01)

CPC (source: EP)
G03F 7/0751 (2013.01)

Citation (search report)

- [X] US 3549368 A 19701222 - COLLINS ROBERT H, et al
- [X] US 4103045 A 19780725 - LESAICHERRE ANDRE, et al
- [X] DE 2001339 A1 19700723 - IBM
- [A] US 3520683 A 19700714 - KERWIN ROBERT E
- [A] D.J. ELLIOTT: "Integrated circuit fabrication technology", 1982, pages 119-121, McGraw-Hill Book Co., New York, US

Cited by
EP0792195A4; CN110908240A; CN108314692A; CN114524841A

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